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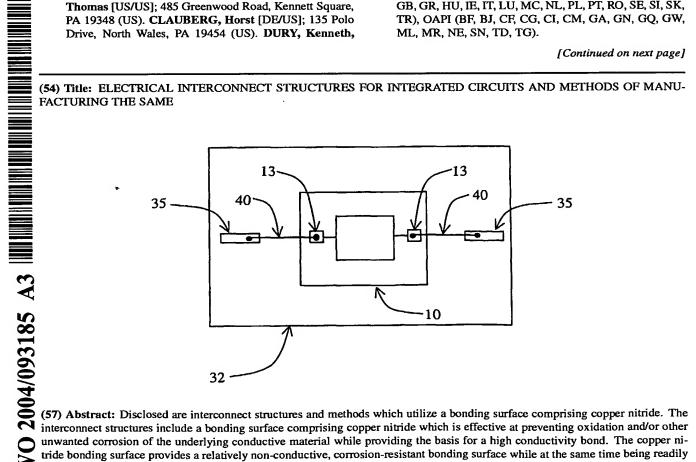
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unwanted corrosion of the underlying conductive material while providing the basis for a high conductivity bond. The copper nitride bonding surface provides a relatively non-conductive, corrosion-resistant bonding surface while at the same time being readily transformed into a conductive layer at or just prior to the time of bonding.



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#### INTERNATIONAL SEARCH REPORT

/US2004/010861

A. CLASSIFICATION OF SUBJECT MATTER
IPC 7 H01L23/485 H01L21/60 H01L21/607 H01L21/603 According to International Patent Classification (IPC) or to both national classification and IPC B. FIELDS SEARCHED Documentation searched other than minimum documentation to the extent that such documents are included in the fields searched Electronic data base consulted during the International search (name of data base and, where practical, search terms used) EPO-Internal C. DOCUMENTS CONSIDERED TO BE RELEVANT Relevant to claim No. Citation of document, with Indication, where appropriate, of the relevant passages Category ° 1-3,X WO 01/01478 A (RAMM JUERGEN ; BALZERS 10-12, HOCHVAKUUM (LI)) 4 January 2001 (2001-01-04) 24-26,38 page 3, line 13 - page 6, line 27; claims 6-9, Y 13-17. 9,19 20,22, 23, 27-31, 34,36,37 Ε & US 2004/087150 A1 (RAMM JURGEN) 1-3, 10-12, 6 May 2004 (2004-05-06) 24-26,38 the whole document Further documents are listed in the continuation of box C. Patent family members are listed in annex. Special categories of cited documents: "T" later document published after the international filing date or priority date and not in conflict with the application but cited to understand the principle or theory underlying the "A" document defining the general state of the art which is not considered to be of particular retevance Invention "E" earlier document but published on or after the International filling date "X" document of particular relevance; the claimed invention cannot be considered novel or cannot be considered to involve an inventive step when the document is taken alone "L" document which may throw doubts on priority claim(s) or which is clied to establish the publication date of another citation or other special reason (as specified) Y document of particular relevance; the claimed invention cannot be considered to involve an inventive step when the document is combined with one or more other such documents, such combination being obvious to a person skilled in the art. "O" document referring to an oral disclosure, use, exhibition or other means document published prior to the International filing date but later than the priority date claimed "&" document member of the same patent family Date of the actual completion of the international search Date of mailing of the international search report 2 November 2004 09/11/2004 Name and mailing address of the ISA Authorized officer European Patent Office, P.B. 5818 Patentlaan 2 NL - 2280 HV Rijswijk Tel. (+31-70) 340-2040, Tx. 31 651 epo nl, Fax: (+31-70) 340-3016 Edmeades, M

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